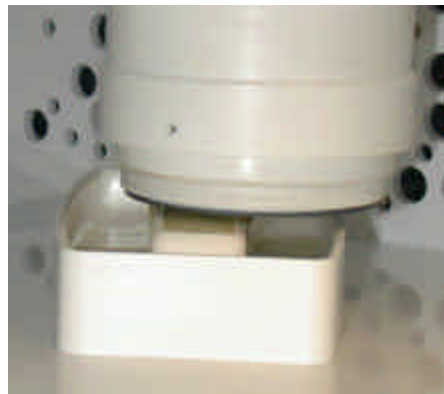


WaveEtch™ pattern etching performance

Matech™'s new WaveEtch™ system introduces two critical advances in wet processing technology. The WaveEtch™ utilizes Linear Scan* wet processing and Dynamic Confinement* technologies to dramatically improve etching performance. The Linear Scan provides a uniform and continuously replenished liquid film for etching that automatically transports used reactants and heat away from the substrate, resulting in unparalleled wet processing uniformity. Combined with Dynamic Confinement, a technology that protects the back side of the substrate, the new WaveEtch™ is the perfect tool for your single sided pattern etching applications. The graph to the right shows the quality that can be achieved on a uniform, sub micron, line-space pattern with a WaveEtch™.

These new technologies are implemented in a fully automated, dry-in-dry-out, cassette-to-cassette processing system. The WaveEtch™ can be configured to work with substrate sizes from 2 to 6 inches and its chemical handling unit can be configured with up to seven channels, providing maximum flexibility.

Contact Matech™ now to increase your wet processing quality and yield!



* Patent Pending



MATECH's Linear Scan technology sets new standards for wet chemical etching!

